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Notice of References Cited		Application No. 08/479,211		Applicant(s) Ohtani et al.	
		Examiner Leon Radomsky		Group Art Unit 1104	
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U.S. PATENT DOCUMENTS					
	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
A	5,529,937	6-25-96	Zhang et al.	437	21
B	5,481,121	1-2-96	Zhang et al.	257	64
C	5,219,786	6-15-93	Noguchi	437	174
D					
E					
F					
G					
H					
I					
J					
K					
L					
M					

FOREIGN PATENT DOCUMENTS						
	DOCUMENT NO.	DATE	COUNTRY	NAME	CLASS	SUBCLASS
N						
O						
P						
Q						
R						
S						
T						

NON-PATENT DOCUMENTS		
	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
U	S. Caune et al., Appl. Surf. Sci., 36(1989)597, "Combined CW laser and furnace annealing of amorphous Si and Ge in contact with some metals".	1989
V	M. Fuse et al., Solid State Phenomena, 37-38(1994)565, "Performance of poly-si TFTs fabricated by excimer laser annealing ... with or without solid phase crystallization"	1994
W		
X		